
Review of Solidstate Photomultiplier

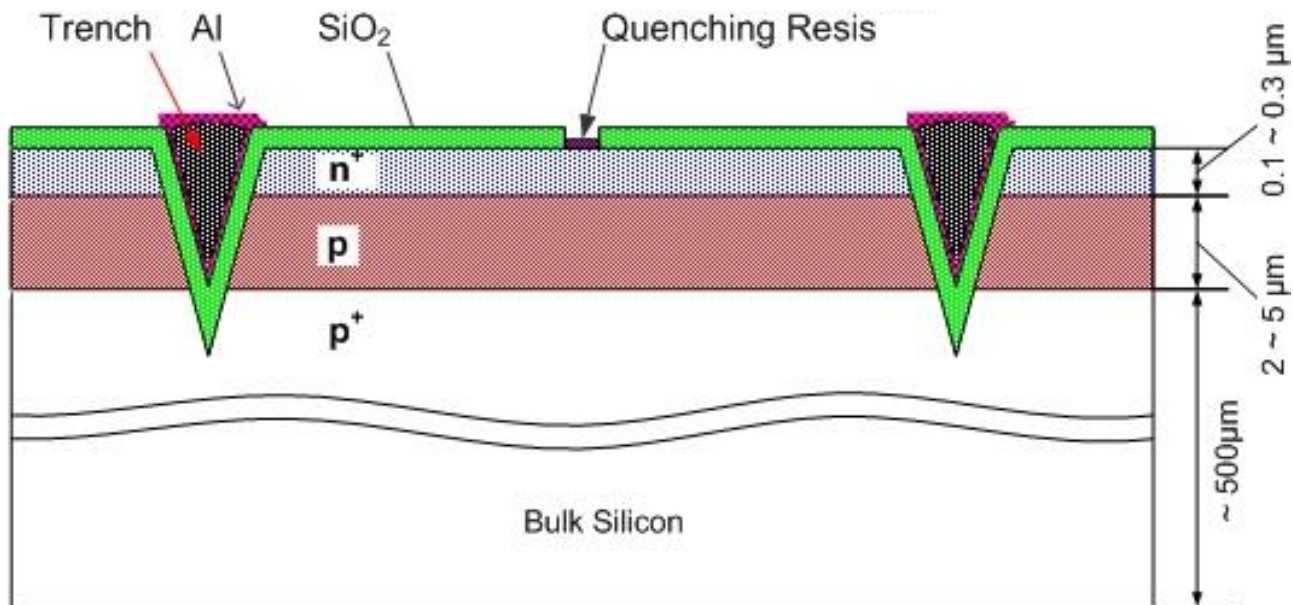
Developments by CPTA & Photonique SA

Victor Golovin – Center for Prospective Technologies & Apparatus (CPTA)
&
David McNally - Photonique SA

Overview

- SSPMs development & status
- Support electronics
- Outlook

$n^+ p p^+$ Structure for Visible Light Applications



Trench Architecture

- High fill / geometric factor
- Low optical cross talk
- Low excess noise
- Uniform Electric field



Visible Light Sensor Line-Up (2008)

Sensor Area	Micro-cell size	Micro-cell count	Geometric Factor
1mm ²	43μm	556	~60%
4.4mm ²	50μm	1764	>70%
9.0mm ²	33μm	8100	>60%



NEW 2009:

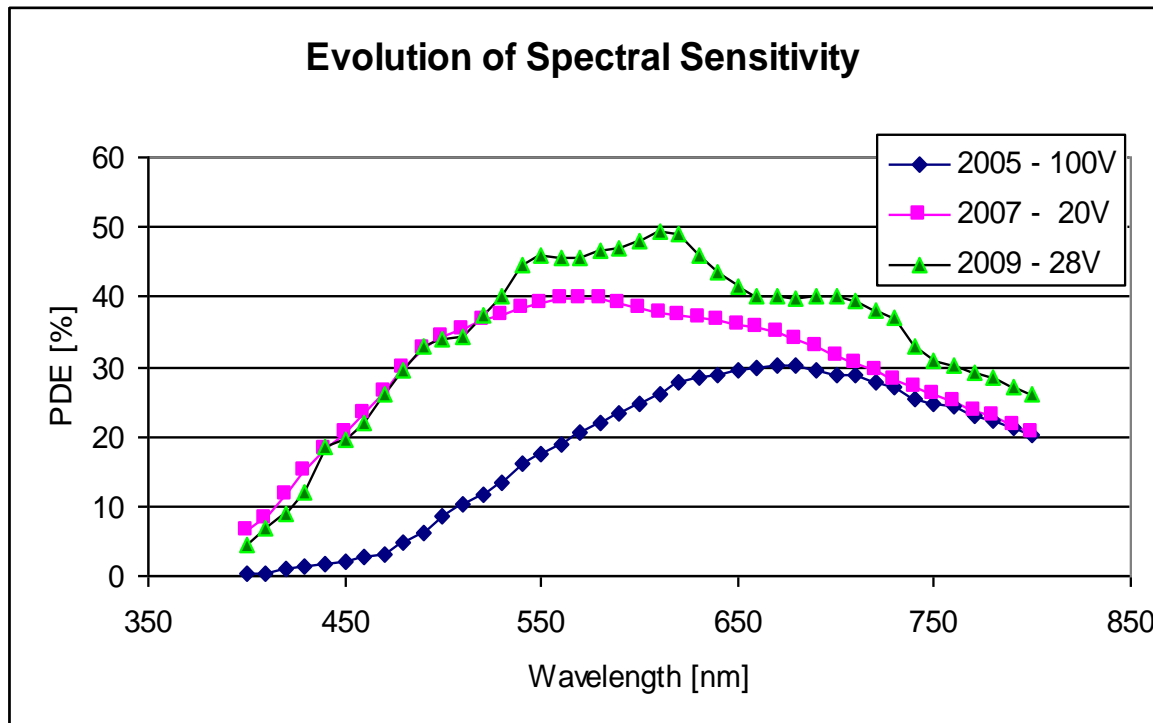
2.5 x 2.5 mm

43μm cell size

~70%

Performance Evolution 2005 - 2009

- Opt. doping concentrations
- Opt. n+ layer thickness
- Impr. n+ p junction
- Impr. trench geometry
- Better field uniformity

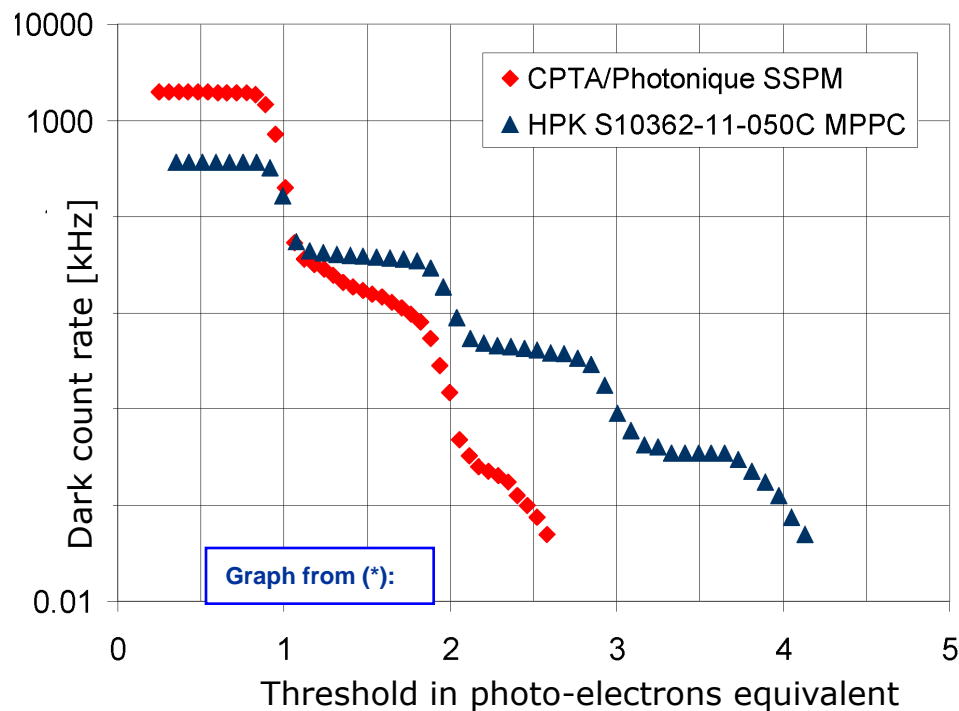


2005:	$V_b = \sim 100V;$	$V_{ov} = V_{bias} - V_b$	up to 4V	or 4% of V_b
2007:	$V_b = \sim 17V;$	$V_{ov} =$	up to 8V	or 45% of V_b
2009:	$V_b = \sim 28V;$	$V_{ov} =$	>10V	and Gain $\sim 1.4 \times 10^6$ in 50ns gate

Optical Cross-Talk

Trench architecture significantly reduces optical cross talk and allows for improved tuning of readout threshold

- **No Trench:**
Crosstalk: **20% ... 30%**
- **With Trench:**
Crosstalk: **1% ... 3%**



(*) Y. Musienko – Advances in multipixel Geiger-mode avalanche photodiodes (silicon photomultipliers); to be published in NIM A (08)

Quenching Resistor

Affects: Cell Recovery Time & After pulsing

Can tune micro-cell quenching resistor value from

0.7M Ω

to

100M Ω

Fast recovery **~70ns**

Modest afterpulsing:

<10% in 100ns gate

Slower recovery **~10 μ sec**

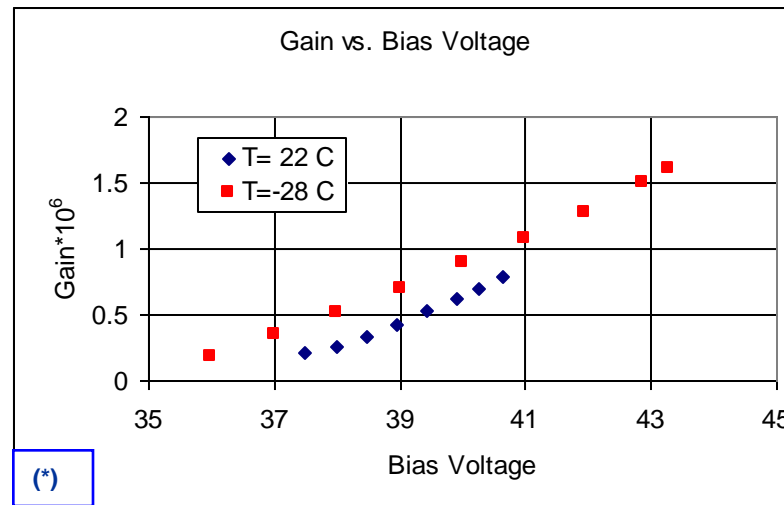
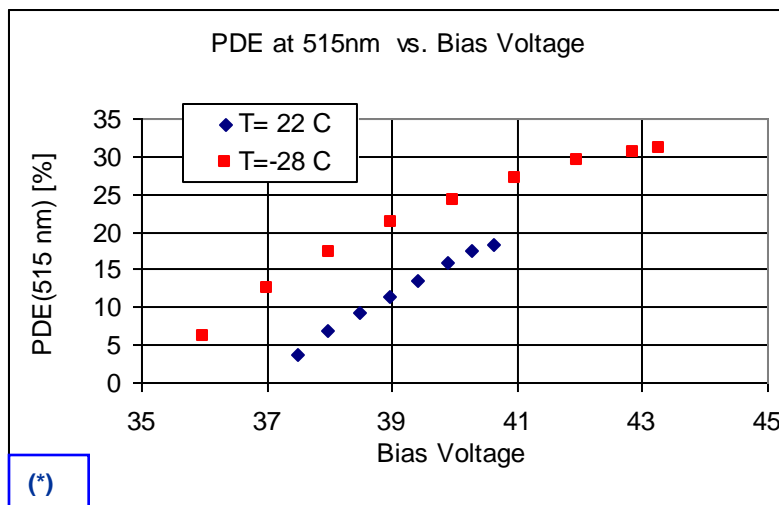
Low afterpulsing

~1-3% in 100ns gate

Note: Micro-cell capacitance **~100fF** ; **“Optimal” value for off-the-shelf: ~1M Ω**

Temperature Stability of Signal Amplitude (I)

$$\text{Amplitude}_{\text{Signal}} = N_{\text{Photons}} \times \text{PDE}(T) \times \text{Gain}(T)$$



T = - 28C°

T = + 22C°

Wide V_{op} range results in reduced slope in the **PDE vs. Bias** and **Gain vs. Bias** curves.

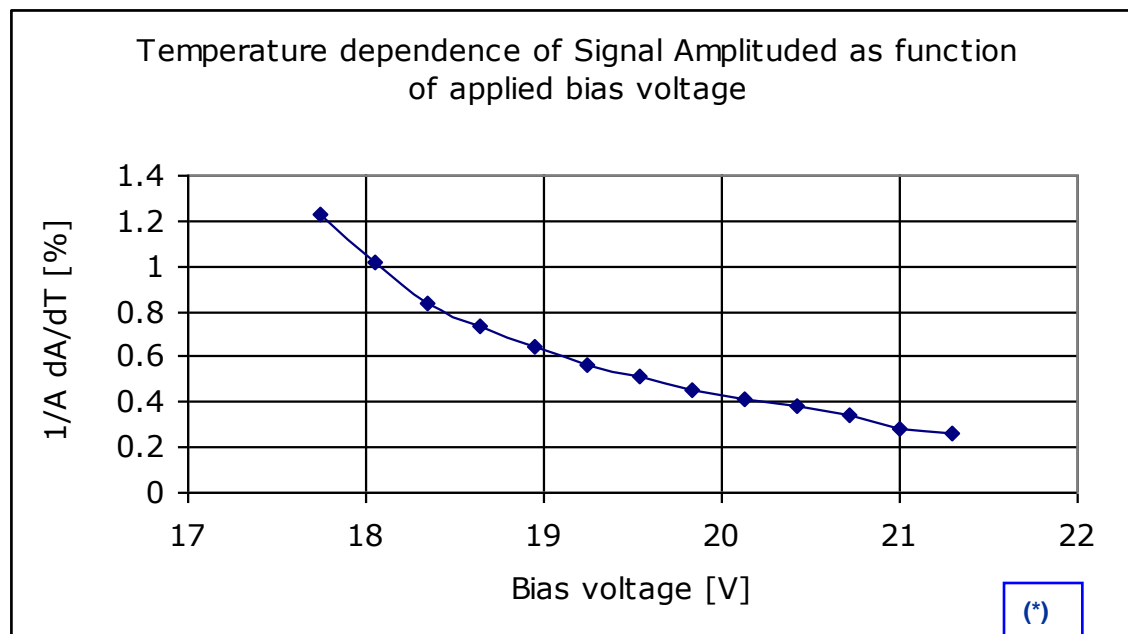
(*): SSPM_050701GR

Temperature Stability of Signal Amplitude (II)

A wide V_{op} range over V_b reduces temperature dependence of signal amplitude

Amplitude – Temperature correlation is $<1\%/C^\circ$ for bulk of operating range.

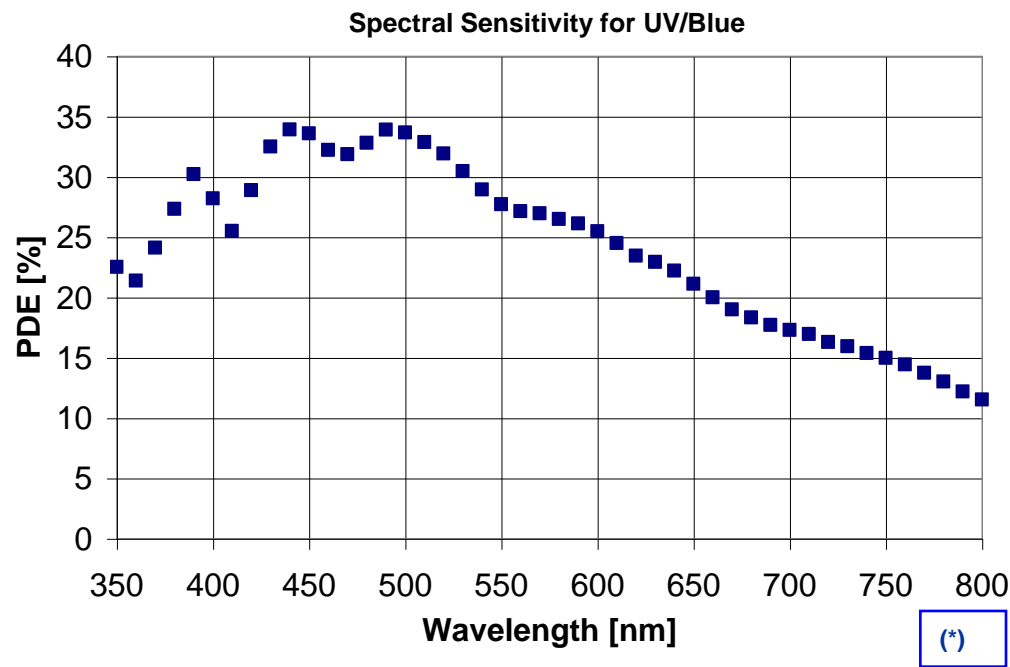
2009 $< 0.5 \%/C^\circ$



(*) SSPM_0701BG

p⁺ p n⁺ (UV/Blue): 2008

- Significantly improved implementation of this structure
- Still fighting against dark counts: 1 ~ 3 MHz / mm²
- Working on wavelength shifter enhanced devices for deep UV applications



T-coeff. of gain	< 1% / C ⁰
Excess noise factor	< 1.1
Rise time	< 700ps

(*) SSPM_0611B14MM

Readout & Support Electronics

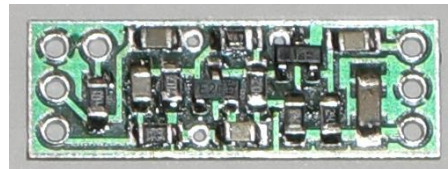
We are developing a comprehensive set of readout solutions

These are available:

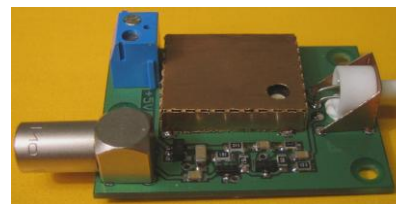
- Turn-key**
- Customized**
- Under license**

Readout & Support Electronics

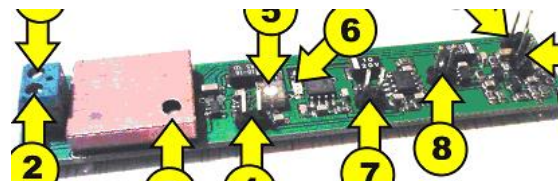
Bias circuit
⊕
Transimpedance amplifier



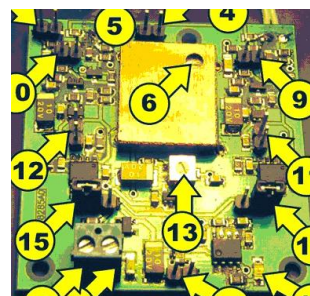
Above
⊕
Temp. Comp. Bias supply



Above
⊕
Threshold Discriminator



Above for Dual Channel
⊕
Coincidence Unit



Outlook

SSPMs - Core sensor developments:

- Higher cell density with peak PDE $\geq 40\%$
- Noise / Dark-count rate reduction
- Small area devices
- Improved sensor packages
- Peltier cooled solutions

SSPM support infrastructure:

- Modular electronics solutions
- Light concentration and focusing

Thank you for your attention

Photonique SA
ch du Grand-Puits 38
1217 Meyrin
Switzerland

Web: www.photonique.ch
Email: info@photonique.ch
Phone: +41 22 777 7357
Fax: +41 22 782 3718
Skype: photonique_sa